

# Quasi-Moseleys law for UTA spectra in high-Z highly ion charge states for high power EUV & soft x-ray sources

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## Abstract

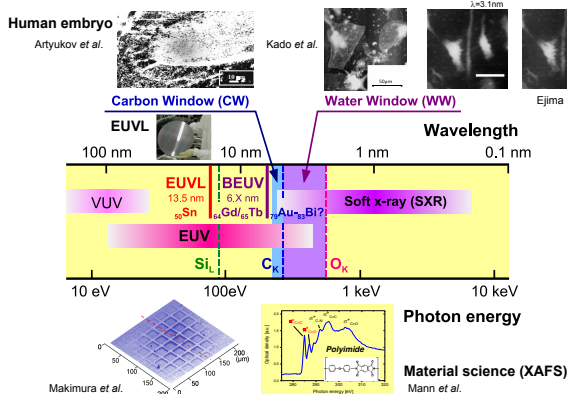
Bright narrow band emission observed in optically thin plasmas of high-Z elements in the extreme ultraviolet spectral region follows a quasi-Moseley's law. The wavelength varies from 13.5 nm to 4 nm as the atomic number ranging from 50 to 83. The range of emission wavelengths available from hot optically thin plasmas permits the development of bright laboratory-scale sources for applications including lithography, x-ray microscopy, and x-ray absorption fine structure (XAFS) determination.

## Summary

- (1) We can select the wavelength of the  $n = 4 - n = 4$  ( $\Delta n = 4$ ) UTA light source by adequate Z-selection of the target element and tune it by control of the laser intensity.
- (2) Quasi-Moseley's law is useful for the estimation of appropriate elements.

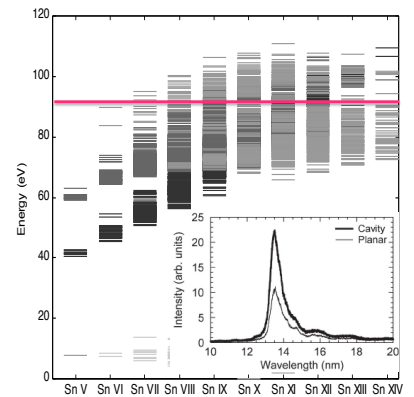
$$\lambda_{\text{UTA}} \text{ (nm)} = 21.86 \times R_{\infty}^{-1} (Z - 23.23)^{-1.52}$$

## Background



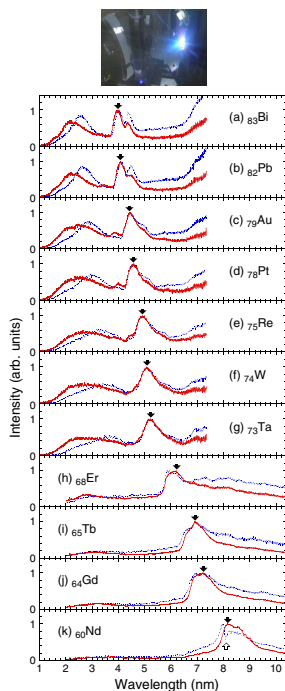
(a) Line spectrum

(b) UTA

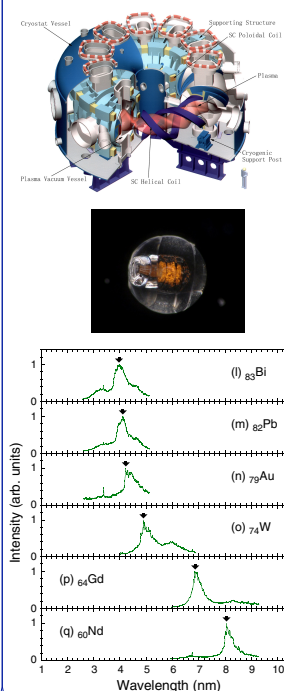


## Results

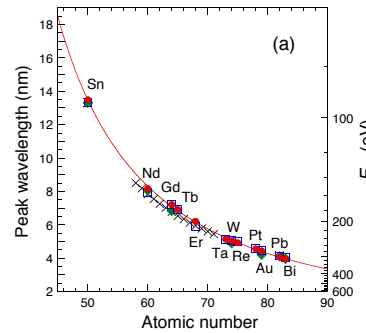
### LPPs (150 ps & 10 ns)



### DPPs (LHD@NIFS, Japan)



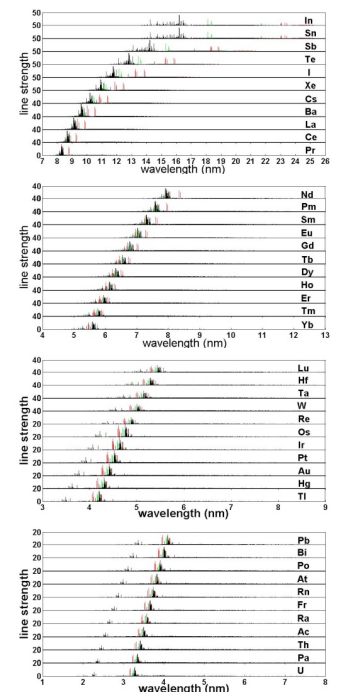
$$\lambda_{\text{UTA}} \text{ (nm)} = 21.86 \times R_{\infty}^{-1} (Z - 23.23)^{-1.52}$$



- Peak wavelength of  $n = 4 - n = 4$  UTAs ( $\lambda_{\text{UTA}}$ ) depends on the atomic number.
- Quasi-Moseley's law was derived from the ps-LPP experimental values.
- UTA peaks of  $Z = 79-83$  were in the water window and  $Z = 75-79$  in the carbon window.
- $n = 4 - n = 5$  UTAs observed in shorter wavelength than  $n = 4 - n = 4$  UTAs show the difference between pulse durations due to the difference of charge state distributions in the plasmas.
- Strong self-absorption effect was observed in the case of  $_{60}\text{Nd}$ .

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### Shorter-wavelength extreme-UV sources below 10nm



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## Quasi-Moseley's law for strong narrow bandwidth soft x-ray sources containing higher charge-state ions

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